	PTO-1449 US Dept. of Commerce		ATTORNEY DOCKET NO.		SERIAL NO.		
Patent and Trademark Office			643	10/602,172			
INFORMATION	DISCLOSURE STA	ATEMENT	APPLICANT Michael B. Korzenski, et	al.			
(use several sheets if necessary)			FILING DATE		GROUP		
		II C	June 24, 2003 PATENT DOCUMENTS	- 47 * *			
EXAMINER	PATENT	0.3.	PATENT DOCUMENTS			FILING	DATE
INITIAL	NUMBER	ISSUE DATE	NAME	CLASS	SUBCLASS	IF APPROPRIAT	
	DOCUMENT	FOREIC PUBLICATION	N PATENT DOCUMEN	TRANSLATION			
	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLAS S	YES	NO
						X (abstract only)	
			ing Author, Title, Journal				
AA AA			nal Damascene Low-K Dielectrochemical Society, Inc.,			ercritical CC)2, Abs
don AB	Supercritical CC	2 Post-Etch Clea ters, et al., pgs. 1	ning of a Patterned Porous	Low-K Dielec	etric, Ashland	Specialty C	hemica
7							
		<u> </u>			· <u>-</u> ····		
<u></u>							
EXAMINER (SYL				DATE CONSIDERED		
	V						
	tial if citation consident of the control of the co		not citation is in conformat				h

SERIAL NO. ATTORNEY DOCKET NO. US Dept. of Commerce Patent and Trademark Office 10/602,172 APPLICANT INFORMATION DISCLOSURE STATEMENT Michael B. Korzenski, et al. GROUP FILING DATE (use several sheets if necessary) June 24, 2003 **U.S. PATENT DOCUMENTS** FILING DATE PATENT **EXAMINER** IF APPROPRIATE **SUBCLASS** CLASS ISSUE DATE NAME NUMBER INITIAL FOREIGN PATENT DOCUMENTS TRANSLATION DOCUMENT **PUBLICATION SUBCLAS** YES **CLASS** COUNTRY DATE NUMBER S $\overline{\mathbf{x}}$ (abstract only) OTHER DOCUMENTS (Including Author, Title, Journal-Date, Page Number, Etc.) Post-Etch Cleaning of 300mm Dual Damascene Low-K Dielectric Structures Using Supercritical CO2, Abs. AA 796, 204th Meeting 2003 The Electrochemical Society, Inc., Robert B. Turkot, Jr., et al. Supercritical CO2 Post-Etch Cleaning of a Patterned Porous Low-K Dielectric, Ashland Specialty Chemical AB Company, D. Peters, et al. DATE CONSIDERED 2n-**EXAMINER** 3-30-05 EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.